L Number	Hits	Search Text	DB	Time stamp
1	2799	250/341.8,306,307,559.3.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/22 15:11
2	87	"critical dimension" AND 250/341.8,306,307,559.3.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/22 15:12
3	93	(ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4 nanometrology) AND 250/341.8,306,307,559.3.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/22 15:12
-	0	scatterometry AND 250/237R.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/26 16:35
-	205	scatterometry	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/26 16:40
-	963	profilometry	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/26 16:40
-	0	250/237R.ccls. AND profilometry	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/26 16:42
-	8	(scatterometry OR profilometry) AND 356/614,616,620.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 13:27
-	8	(scatterometry OR profilometry OR reflectometry) AND 356/614,616,620.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 14:09
-	4106	(ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/07 11:28
-	1	((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension)) AND 250/237R.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 14:11
-	331	250/$.ccls. AND ((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 14:11
-	224	(wafer substrate (integrated ADJ circuit)) AND (250/$.ccls. AND ((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 14:12
-	142	((wafer substrate (integrated ADJ circuit)) AND (250/$.ccls. AND ((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension)))) AND @pd<20020225	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 15:33
-	714	((determin$5 measur$4) NEAR4 (period pitch dimension)) AND ((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 15:32
-	219	356/$.ccls. AND (((determin$5 measur$4) NEAR4 (period pitch dimension)) AND ((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 15:33

-	131	(356/$.ccls. AND (((determin$5 measur$4) NEAR4 (period pitch dimension)) AND ((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4) AND (pitch OR dimension)))) AND @pd<20020225	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/09/03 15:33
-	672	356/614,616,620.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/07 11:28
-	1144	250/237R.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/07 11:28
-	1	("6433878").PN.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/07 14:23
-	9	("4870289" | "5164790" | "5413884" | "5576829" | "5879844" | "5962173" | "5963329" | "6137570" | "6187483").PN.	USPAT	2003/10/07 14:23
-	17	(ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4 nanometrology) AND (356/614,616,620.ccls. 250/237R.ccls.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/22 15:12
-	8	((feature OR structure) WITH (dimension OR measurement OR pitch)) AND ((ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4 nanometrology) AND (356/614,616,620.ccls. 250/237R.ccls.))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/09 17:15
-	1	("6433878").PN.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/14 15:02
-	1735	(356/399,495,503,625,634,635,630,640).CCLS.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/20 17:39
-	161	(ellipsomet$4 reflectomet$4 profilomet$4 scatteromet$4 nanometrology) AND ((356/399,495,503,625,634,635,630,640).CCLS.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/20 17:40
-	9	("5867276" | "5877880" | "5880838" | "6051348" | "6081334" | "6141107" | "6245584" | "6383888" | "6423977").PN.	USPAT	2003/10/21 13:00
-	11107	"integrated circuit" AND pitch AND pattern	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/21 15:13
-	43	scatterometry AND ("integrated circuit" AND pitch AND pattern)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/10/22 15:10

C:\APPS\EAST\Workspaces\10083877.wsp